

Thermal Atomic Layer Deposition of Silicon Carbonitride Using Carbon-Containing Silicon Precursor

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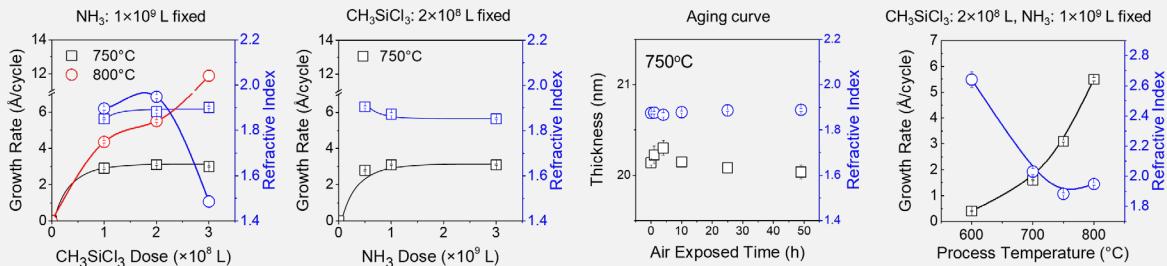
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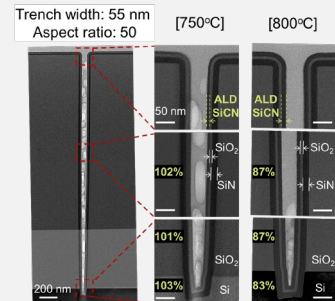
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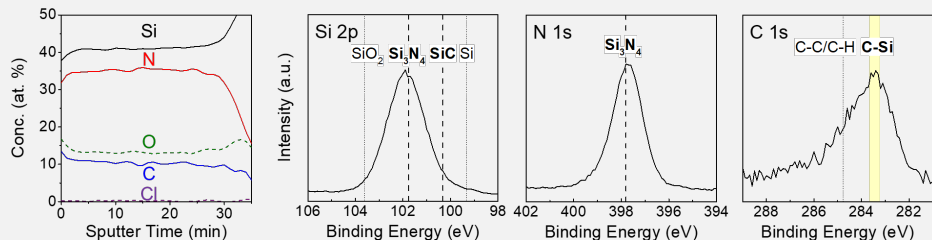
ALD growth kinetics



Step coverage



XPS analysis



E-test

